

Docket No.: 2328-049PATENT

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :  
Tuqiang NI et al :  
Serial No. 09/689,616 : Group Art Unit: 1763  
Filed: October 13, 2000 : Examiner: L. Alejandro  
For: VACUUM PLASMA PROCESSOR HAVING A CHAMBER WITH ELECTRODES  
AND A COIL FOR PLASMA EXCITATION AND METHOD OF OPERATING  
SAME

AMENDMENT

Assistant Commissioner for Patents  
Washington, D. C. 20231

Sir:

In response to the June 27, 2002 Office Action, please amend  
the application as follows:

IN THE CLAIMS:

Please amend claims 7, 8, 29, 30 and 31 as follows:

7. (amended) The vacuum plasma processor of claim 3 wherein  
the dielectric window, semiconductor member and non-magnetic metal  
arrangement are in a roof structure of the chamber, the chamber  
having a center portion, the coil having an interior portion that  
is spaced from the chamber center portion so peripheral portions of  
the semiconductor member are not outside the coil interior portion,  
the non-magnetic metal arrangement having peripheral portions  
spaced from the chamber center portion by approximately the same